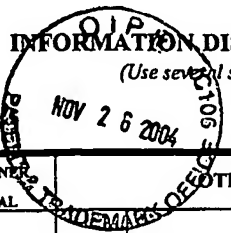
				Docket Number (Optional) 2003US313		Application Number 10/748,778		
				Applicant(s) Ralph R. DAMMEL				
				Filing Date December 29, 2003		Group Art Unit 1752		
U.S. PATENT DOCUMENTS								
*EXAMINER INITIAL	REF	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE	
SJL		5,019,660	5/28/1991	Chapman et al.	585	22		
↓		6,783,589 B2	8/31/2004	Dahl et al.	117	84		
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*EXAMINER INITIAL	REF	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE	
SJL		2002/0177743 A1	11/28/2002	Dahl et al.	585	16		
↓		2003/0199710 A1	10/23/2003	Liu et al.	562	498		
FOREIGN PATENT DOCUMENTS								
	REF	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	Translation YES NO	
OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)								
SJL		"Diamondoid Hycrocarmons – Delving into Nature's Bounty", Alan P. Marchand, Science, Vol. 299, 3 January 2003, pps. 52-53 "Isolation and Structure of Higher Diamondoids, Nanometer-Sized Diamond Molecules", J. E. Dahl et al., Science, Vol. 299, 3 January 2003, pps. 96-99						
↓								
EXAMINER <i>[Signature]</i>				DATE CONSIDERED 1-23-05				
EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP Section 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.								

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Applicant(s) Ralph R. DAMMEL	
Filing Date December 29, 2003	Group Art Unit 1752

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)		
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SJL		"A Novel Polymer For A 193-nm Resist", K. Nozaki et al., Journal of Photopolymer Science and Technology, Vol. 9, No. 3 (1996), pps. 509-522
		"Design of cycloolefin-maleic anhydride resist for ArF lithography", J-C. Jung et al., SPIE, Vol. 3333 Part 1, 23-25 February 1998, pps. 11-25
		"Adhesion Characteristics of Alicyclic Polymers for use in ArF Excimer Laser Lithography", K. Nakano et al., SPIE, Vol. 3333 Part 1, 23-25 February 1998, pps. 43-52
		"Reactive ion etching of 193 nm resist candidates: current platforms, future requirements", T. Wallow et al., SPIE, Vol. 3333 Part 1, 23-25 February 1998, pps. 92-101

EXAMINER <i>Sir J. Lu</i>	DATE CONSIDERED <i>1-23-05</i>
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*EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP Section 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.